

Form PTO-1449 (Modified)	Attorney Docket No.: 07620009C2	Serial No.: To Be Assigned
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	Applicant: Darren Kenneth ROGERS, <i>et al.</i>	
(Use several sheets if necessary)	Page 1 of 1	Filing Date: Concurrently Herewith
		Group: To Be Assigned

REFERENCE DESIGNATION		U.S. PATENT DOCUMENTS					
EXAMINERS INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLAS S	FILING DATE (IF APPRO.)
MK		3,309,437	03/1967	Harnett, John P.	423	460	

FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
MK		GB 14899690	10/1977	GB	----	----	<input type="checkbox"/>	<input type="checkbox"/>
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OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)			
			Kirk-Othmer, Encyclopedia of Chemical Technology, 4 th Edition, Volume 6, John Wiley & Sons, NY., Application of Coal Petrology & Petrography, pages 429-434 & 454-455, 1993.
MK			SU 973,509A, ENGLISH ABSTRACT, (BELIO), 11-1982.
MK			SU 536,148A, ENGLISH ABSTRACT, (DEMII), 01-1977.
MK			JP 53-094,313A, ENGLISH ABSTRACT, (IBIG), 08-1978.
MK			CN 1290755A, ENGLISH ABSTRACT, (YELLI), 04-2001.

EXAMINER /Malini Krishnan/	DATE CONSIDERED 12/11/2006
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.